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# MEMS Metrology

Presented by James Nichols  
Advisor: Dr. Thomas Kurfess  
October 29, 2002

# Overview

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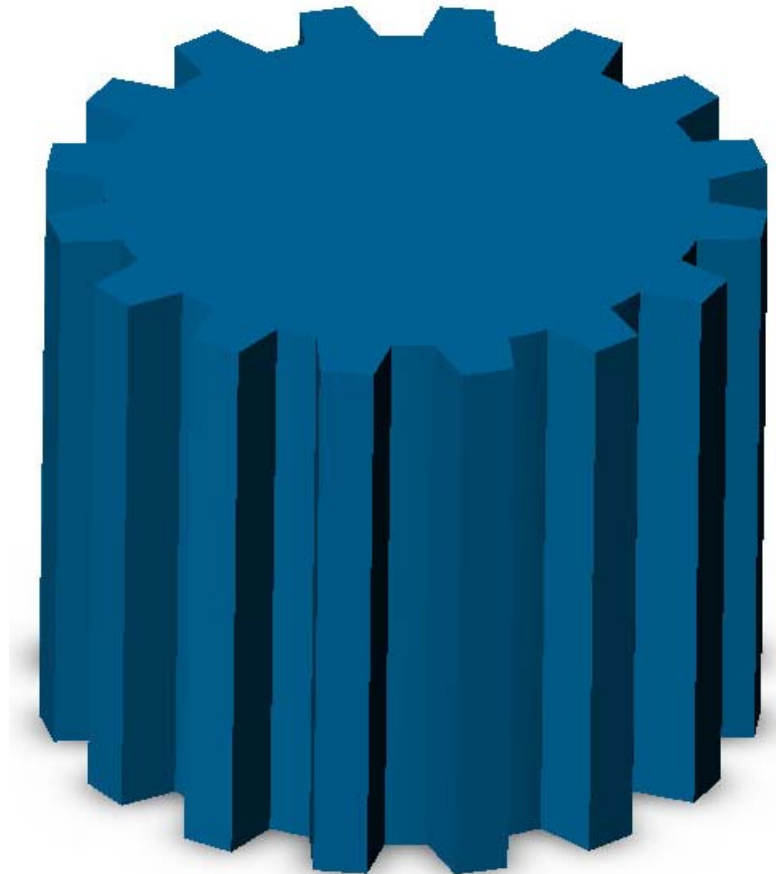


- Background information
- Current problems
- Objectives of research
- Expected Contributions

# Background

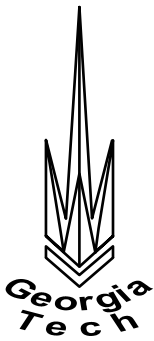
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- LIGA
  - German acronym for lithography (lithographie), electrodeposition (galvanoformung), and molding (abformtechnik)
  - Fabrication method used to manufacture high-aspect ratio MEMS (micro-electro-mechanical systems)



# Background

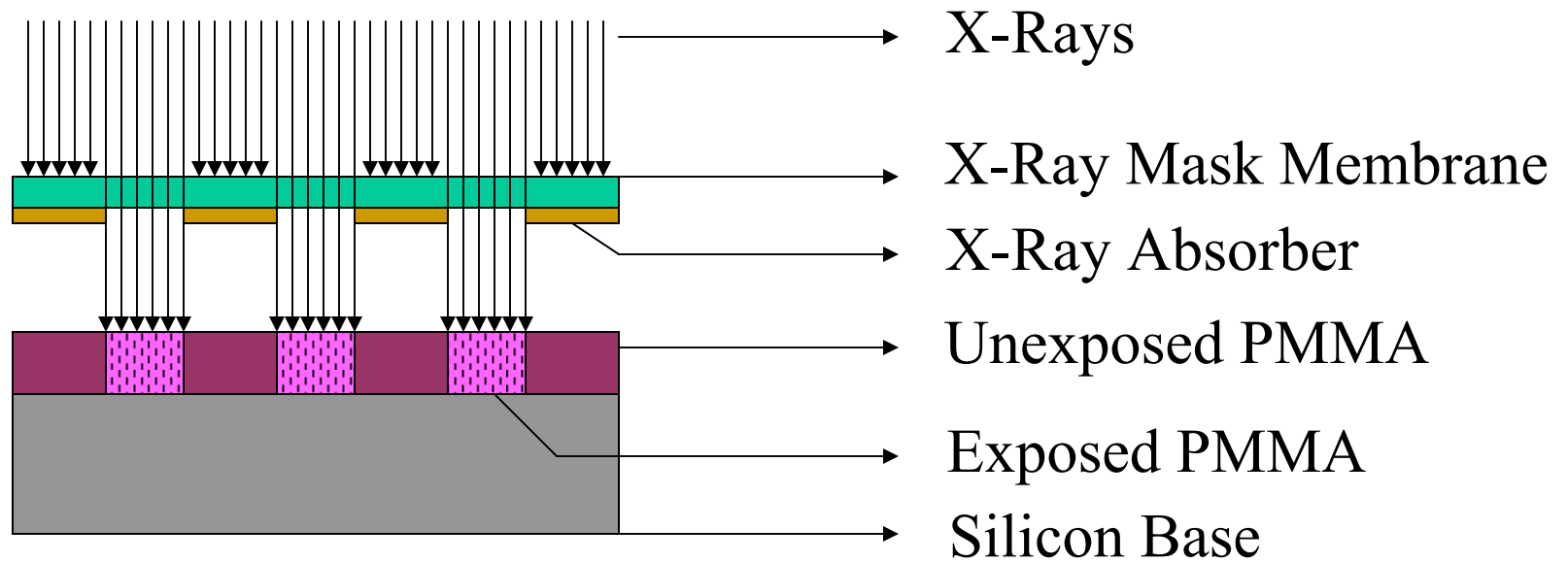
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- LIGA Process
  - LIGA Mask Fabrication
  - LIGA Substrate Preparation
  - X-Ray Exposure
  - X-Ray Resist Development
  - Electroplating and Planarization

# Background

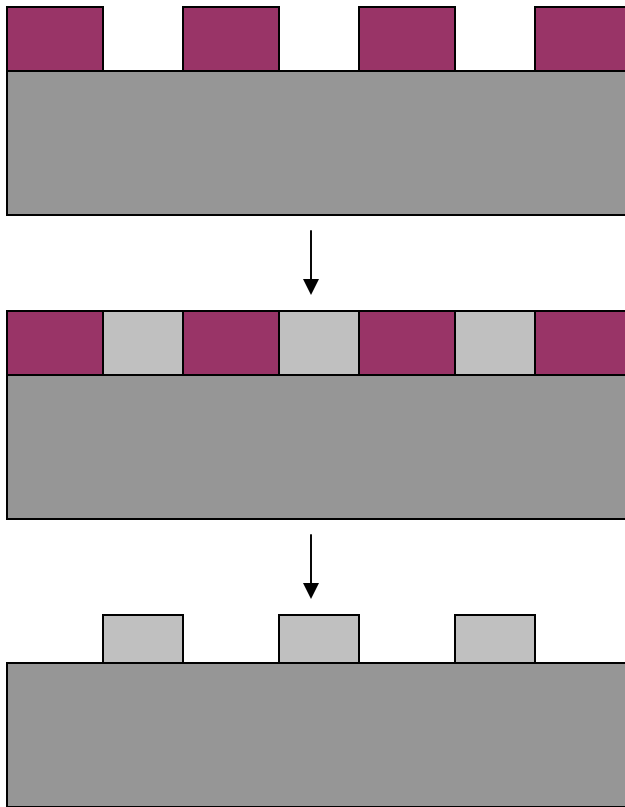
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Illustrative Overview

# Background

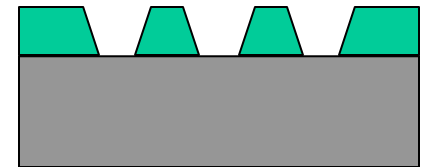
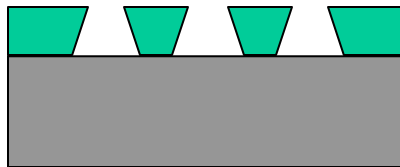
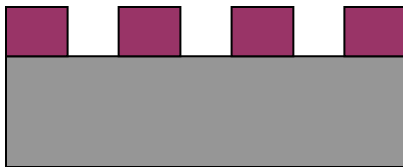
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Illustrative Overview

# LIGA Problems

- Various geometry outcomes due to overexposure, development, and post-processing



Ideal



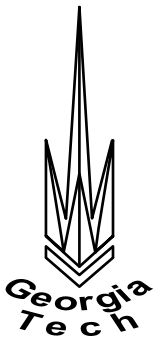
Overcut



Undercut

# LIGA Metrology

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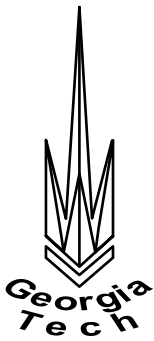


- Currently, no suitable 3-D data acquisition techniques for part verification
- Difficult to determine sidewall characteristics of high-aspect ratio parts
- Most analyses of parts come from 2-D acquisition methods



# LIGA Metrology

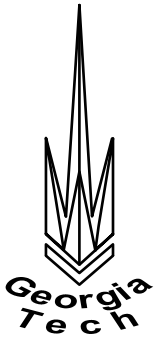
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- Current 2-D techniques
  - SEM
  - Traditional optical microscopy
  - Stylus profilometry
- Proposed 3-D techniques
  - White-light interferometry
  - Atomic force microscopy
  - Digital volumetric imaging
  - X-Ray tomography
  - Micro-interferometry

# LIGA Metrology

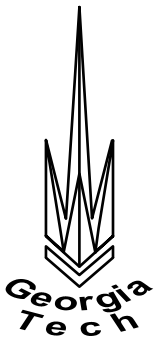
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- 2-D limitations
  - Only captures 2-D data
  - Relies heavily on image processing
    - Edge detection errors
    - Focus errors
    - Lens aberrations

# LIGA Metrology

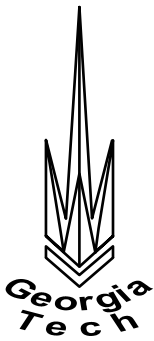
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- Issues with proposed 3-D methods
  - White light interferometry – limited to relatively flat surfaces
  - Atomic force microscopy – lack of Z-range and slow
  - Digital volumetric imaging – destructive and post-processing errors
  - X-Ray tomography – resolution and post-processing errors
  - Micro-interferometry – technology not quite there yet

# Proposed Research

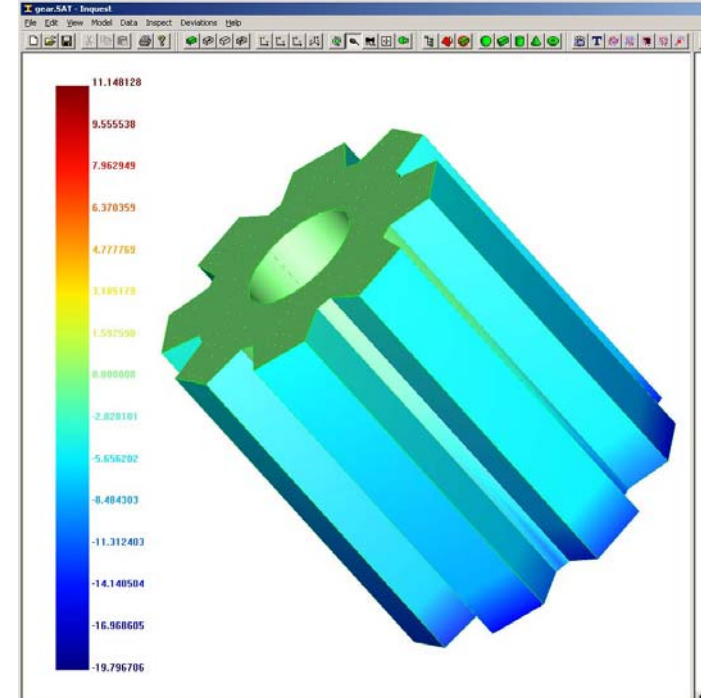
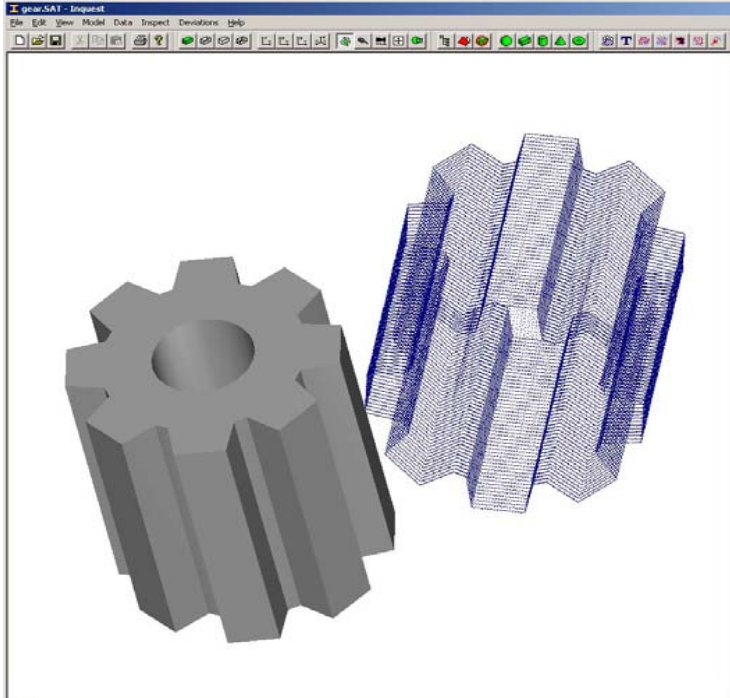
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- Find artifacts of known dimensions that can be analyzed by most of the proposed 3-D analysis methods and exhaustively compare
- Develop LIGA test structures which will allow for thorough comparison of 2-D and 3-D techniques
- Develop software which can analyze both 2-D and 3-D data sets in one environment
- Develop methodology to correctly qualify the LIGA process
- Use methodology to improve process parameters of the fabrication method

# Current Status

- Developing software package to analyze both 2-D and 3-D CAD models and pointclouds



# Expected Contributions

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- Robust software program to analyze 2-D and 3-D data sets
- Reliable methodology to inspect high-aspect ratio MEMS devices
- Improve fabrication steps by “closing the loop” in the manufacturing process